



## Joint Symposium on Direct Write, Optical, Ion and Electron Beam Lithography Thursday, 03.12.2020

This symposium features technical experts and customers from Nanoscribe, micro resist technology, Heidelberg Instruments, GenISys and Raith who will describe the spectrum of latest, state-of-the-art direct-write capabilities.

09:30 – 09:40

### Welcome and Introduction

09:40 – 10:10

### Highlights in photopolymer development for advanced micro & nanopatterning technologies

*Anja Voigt, micro resist technology GmbH*

10:10 – 10:40

### Nanofabrication for quantum computing

*Michael Kahl, Raith GmbH*

10:40 – 10:50

### Break

10:50 – 11:20

### Towards photonic neuromorphic computing

*Prof. Dr. Wolfram Pernice, WWU Münster*

11:20 – 11:50

### 3D Laser Lithography of Stimuli-Responsive Hydrogels

*Marc Hippler, KIT Karlsruhe*

11:50 – 12:20

### Material Innovations for 3D Microprinting

*Jochen Zimmer, Nanoscribe GmbH*

12:20 – 13:30

### Lunch Break

13:30 – 14:00

### Electron Beam Lithography Software Enabling Quantum Devices

*Nezih Unal, GenISys GmbH*

14:00 – 14:30

### From electrons to photons - applications for direct write lithography

*Helmut Schift, Paul Scherrer Institut, Villigen PSI, Switzerland*

14:30 – 15:00

### Latest Results and New Options in Advanced Microfabrication

*Daniel Braun, Heidelberg Instruments*

15:00 – 15:10

### Break

15:10 – 16:00

### Process Clinic (open discussion about process related challenges)

